

**MEDC-104**

M.E./M.Tech. (First Semester)

EXAMINATION, Dec 2010

(Grading/Non-Grading)

**VLSI DESIGN**

*Time: Three Hours*

*Maximum Marks: GS:70*

**Note:** Attempt any five questions.

1. (a) Obtain the nMOS enhancement transistor threshold voltage equation.  
(b) Calculate native threshold voltage for a n-transistor at  $300^0\text{K}$  for a process with a Si substrate with  $N_A = 1.5 \times 10^{16} \text{ cm}^{-3}$ , a  $\text{SiO}_2$  gate oxide with thickness  $200 \text{ \AA}$ . { Assume  $\phi_{ms}$  (work function) = - 0.9,  $\phi_{fc} = 0$  }.
2. (a) What are the various processes of fabrication of CMOS? Explain any *one* of them with neat diagram.  
(b) Explain the following:
  - i. Oxidation
  - ii. Ion implantation in brief
3. (a) Explain various power dissipations in a CMOS circuit.  
(b) What is Transistor Sizing? Explain with examples.
4. (a) Explain noise margin of an inverter circuit with suitable diagram and expression.  
(b) Explain what is “yield” in the manufacture of VLSI structures. How do the various parameters affect it?
5. (a) Draw the architecture of field programmable gate arrays (FPGAs) and explain the following:
  - i. Programmable interconnects
  - ii. IOBs
  - iii. CLBs  
(b) Give the applications of FPGAs.
6. (a) Explain the following:
  - i. Pass Transistor Logic
  - ii. Dynamic Logic
  - iii. Pseudo-nMOS Logic
7. (a) Explain the data path operations in CMOS sub-system design.  
(b) Design a 32 bit parallel adder optimized for speed, single cycle operation and regularity of layout.

8. Write short notes on any *three* of the following:

- i. MOS capacitor
- ii. Sea of gates
- iii. FSM
- iv. Network Isomorphism
- v. NAND and NOR logic gate design using CMOS